Application No. 10/811,469

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AMENDMENTS TO THE CLAIMS

This listing of claims replaces all prior versions, and listings, of claims in the application.

- (Previously Presented) A positive working heat-sensitive lithographic printing plate precursor comprising a support having a hydrophilic surface and a coating provided on the hydrophilic surface, said coating comprising:
 - -an infrared light absorbing agent,
 - -an oleophilic resin soluble in an aqueous alkaline developer,
 - -a developer resistance means and

wherein said spacer particles comprise cross-linked polysiloxane and have an average particle size is between 1 μm and 7 μm .

- (Canceled). 2.
- (Original) A positive working heat-sensitive lithographic printing plate precursor according to claim 1 wherein said cross-linked polysiloxane is a cross-linked polyalkylsiloxane.
- (Original) A positive working heat-sensitive lithographic printing plate precursor according to claim 1 wherein said coating has a layer thickness comprised between 0.6 g/m^2 and 2.8 g/m^2 .
- (Original) A positive working heat-sensitive lithographic printing plate precursor according to claim 1 wherein said coating comprises at least two layers and wherein said spacer particles are present in at least one of the layers of the coating.
- (Original) A positive working heat-sensitive lithographic printing plate precursor according to claim 1 wherein the amount of said particles in the coating is between 5 and 200 mg/m².
- (Original) A positive working heat-sensitive lithographic printing plate precursor according to claim 1 wherein said developer resistance means is a polymer comprising siloxane or perfluoroalkyl units.

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- 8. (Original) A stack comprising a plurality of positive working heat-sensitive lithographic printing plate precursors, according to claim 1, wherein adjacent plate precursors are separated by an interleave.
 - 9. (Original) A package comprising a stack according to claim 8.
 - 10. (Canceled).
 - 11. (Previously Presented) A method for improving the scuff-mark resistance of a positive working heat-sensitive lithographic printing plate precursor, the precursor comprising a support which includes a hydrophilic surface and a coating provided on the hydrophilic surface, the method comprising providing a support and hydrophilic surface, preparing a coating comprising: an infrared light absorbing agent, an oleophilic resin soluble in an aqueous alkaline developer, a developer resistance means, and spacer particles, wherein the spacer particles comprise cross-linked polysiloxane and have an average particle size between 1 μm and 7 μm, and applying the coating onto the hydrophilic surface.
 - 12. (New) A method of preparing a positive working heat-sensitive lithographic printing plate precursor comprising a support having a hydrophilic surface and a coating provided on the hydrophilic surface, the method comprising providing a coating comprising:
 - cross-linked polysiloxane spacer particles having an average particle size between 1 μm and 7 μm ,
 - an infrared light absorbing agent,
 - an oleophilic resin soluble in an aqueous alkaline developer, and
 - a developer resistance means.